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Title

Preliminary design of a set of four beamlines for the DLSR upgrade of the advanced light source

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Preliminary design of a set of four beamlines for the DLSR upgrade of the Advanced Light Source

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Advances in Computational Methods for X-Ray ptics/V SPIE Optics+Photonics 2020 (Virtual), August 25th, 2020

Upgrade of the Advanced Light Source

ALS-U: updating the ALS to a 4th generation Light Source

- DLSR upgrade of the storage ring
 - E = 2.0GeV (vs. 1.9GeV currently)
 - 9-bend achromat
 - Emittance: ϵ = 75 pm.rad (rms)
 - $-\eta = 1$ coupling (round beam)
 - $-N_{b} = 284$ bunches, I = 500mA
- 4 new beamlines
- Soft x-ray facility
- completion 2025





Specification requirements for new beamlines

- Reuse existing facilities: the ALS
 - straight sections do not move
 - -bend magnet beamlines move slightly
- New beamlines must fit on experimental floor (L=30m)
- Beam and energy resolution to match scientific needs
 - moderate energy resolution (more flux)
 - extreme power density on the sample



Four new and upgraded beamlines

4 beamlines and 7 branches

• FLEXON

- Branch 1: scattering 400–1400 eV, >5000:1 RP, 15 μm focus,
- Branch 2: in development

• Tender

- Branch 1: imaging,
- Branch 2: scattering,

• COSMIC

imaging,

• MAESTRO

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- Branch 1: μARPES
- Branch 2: nano-ARPES

2—8 keV, >5000:1 RP, <3 μm focus 1—5 keV, >5000:1 RP, <3 μm focus

250—2500 eV, >5000:1 RP, 12µm focus size

60—600 eV, >15000:1 RP, 10 μm focus size 60—600 eV, >15000:1 RP, 10 μm focus size

Coherence

 Very high coherent fraction for soft x-ray operation (>50%)

 $Σ = (σ_p^2 + σ_e^2)^{1/2}$





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filament beam size and divergence





Coherence in the upper part of the spectrum

At higher harmonics, the effect of the energy spread in the electron beam can dominate the photon beam emittance, but still a good coherent fraction at higher energy





Undulator radiation brightness and coherence near the diffraction limit Richard P. Walker doi.org/10.1103/PhysRevAccelBeams.22.050704 Physical Review Accelerators And Beams 22, 050704 (2019)

4000

5000

zero E spread

e-beam size (H)

7000

8000

Beamline design

Diffraction-limited performances:

- Minimal number of optics (2H+2V)
 - avoid mirror figure error
 - avoid vibration
- Keep beam round
- Adjustability
 - Vertical beam adjustment: VIA-VLS monochromator
 - Horizontal beam adjustment : Adaptive Optics

Beamline layout



Soft x-ray beamlines

- VIA-VLS grating monochromator
 - -dispersion and focusing
 - -for flexibility, heatload compensation
- Round beam:

resolving power \approx $p \cdot V(g_0(c^2-1)/L_u) \cdot \pi/(2 \cdot 2.35)$ demag = $c \cdot p/q$ light efficiency 1/c

> W. Jark J.Synchrotron Rad. (2019) 26, 1181 doi.org/10.1107/S1600577519004120

matching of the H and V demagnification





Round beam

- Exit slits do:
 - spectrally filter the dispersed photon energy
 - spatially filter the beam and select coherence
- Effect on vibrations
 - since the beam is has sharper features,
 vibrations play a bigger role









Tender beamline



Liquid Nitrogen-cooled white beam mirror

- ALS-U Insertion device: Elliptically Polarizing Undulators
 - fast switching between polarization is such there is a spatially varying heatload
- Using nitrogen cooled white beam mirror to limit aberrations
 - Heatload simulations using SRW/SRCalc
 - FEA simulations using ANSYS
 - Optimization using Strehl ratio
 - Validation using OASYS widget



see talk #11491-14



A cantilevered liquid-nitrogen-cooled silicon mirror for the Advanced Light Source Upgrade. G. Cutler, D. Cocco, E. DiMasi, S. Morton, M. Sanchez del Rio & H. Padmore (2020). J. Synchrotron Rad. 27, doi.org/10.1107/S1600577520008930. Prelimination

Compensation of thermally-induced aberrations

White beam mirror

see talk #11493-4

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– compensation using deformable mirror



- Monochromator pre-mirror
 - compensation using adaptive VLS grating trajectory

Optical simulations - raytracing

Shadow/OASYS

- check nominal size
- figure error
- grating error
- misalignment
- deformation

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corrected beam

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Optical simulations – resolving power

- Resolving power with:
 - mirror error figure
 - ruling error

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Mirror figure error

- Superpolished mirrors: not much data available
- depends a lot on vendors, need to use "comparable" optics
- DABAM global or local



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new easy import/export tool

31452185 0.00

-25.450165 0.00

-24 45004 0.00

Modify

		OABAM Prepare Profile		
Export Output Use of the Wi	rt Calculate Export O	Output Use of the Widget	Info Heights Profile Slopes Profile PSD Heights	
	Create E	DABAM files	profile results	
000838 000881 000800 000822 000875 000876 000976 001950 001950 00195100000000000000000000000000000000	Cle	ar info	Data File: <none>.dat Metadata File: <none>.txt Scan length: 250.001 mm Number of points: 251 No detrending applied.</none></none>	
	Output File Root /Users/av	vojdyla/dabam-07101a		
	Export DABAM file			
	Year of fabrication		Slopes profile:	
	Surface shape	cylindrical 👻	from PSD: 2.142 urad	
	Function	collimating mirror *	Peak-to-valley: no detrend: 9.758 urad with detrend: 9.758 urad	
	Length in SI units [m]	0.2	Skewness: 0.256, Kurtosis: -0.319 PSD power law fit: beta:2.556, Df: 1.222	
	Width in SI units [m]		Autocorrelation length:0.031	
	Thickness in SI units [m]		Stbev of heights profile: 75.505 nm from PSD: 86.001 nm Peak-to-valley: no detend: 222.104 nm with detrend: 222.104 nm Skewness: -0.057, Kurtosis: -1.481 PSD power law fit: beta:4.963, 0F: 0.018 Autocreatelistic length 0.06	
	Optical length in SI units [m]			
	Substrate (e.g. Si)	glidcop		
	Coating (e.g. Pt)	Rh		
	Facility (e.g. ESRF)	ALS		
	Instrument type used	LTP		
	Polishing method			
	Environment	unknown 👻		
	Date of measurement YYYM	DD		
	User example			
	User comment			
	User name	awojdyla		
Select action: *				

Alignment tolerances

Limit degrees of freedom but not too much



• Tolerance budget: $\Delta \theta = 0.32 \cdot 2L_u \cdot Mag^2 \theta / (4\pi q)$ (based on depth of focus)



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Optical simulations – Wavefront propagation

- SRW tool of reference (within Sirepo or OASYS)
 - -evaluation of flux
 - evaluation of height error
 - evaluation of partial coherence (e-beam emittance and E spread)



Optical simulations – Light efficiency

- Mirrors reflectivity from XOPPY or xrt
 - overall efficiency
 - monochromator trajectory
 - -harmonic suppression





19

RCWA simulation for gratings: RETICOLO (Matlab)



Diagnostics

• DiagOn

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- -alignment
- diagnostics of undulator
- Wavefront sensor

LS-U

- intermittent wavefront sensor (shearing, 1D)

reflective shearing grating





K=2.14

Intensity <ph/s/mm²>, total: 1.58e+16 ph/s

multilayer





Intensity <ph/s/mm²>, total: 1.58e+16 ph/

position R [mm

Conclusion

- ALS-U diffraction-limited beamlines have specific constraints, old (reuse of facility) and new (round beam)
- New tools were developed for the preliminary design of ALS-U, covering optical and opto-mechanical aspects
- Diagnostics and correction are important to ensure diffraction-limited beam quality



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ALS-U Beamline and Optical Systems Team December 2019 (left to right) Albert Sheng, Sooyeon Park, Joe Tocci, Antoine Wojdyla, Dima Voronov, Henry Alvarez, Grant Cutler, Manuel Sanchez del Rio, Alastair MacDowell, Jeff Takakuwa, Simon Morton, Diane Dryant, Howard Padmore, Elaine DiMasi, Ken Goldberg, Arnaud Allezy, Dean Kurilich, Maxime Bergeret, Lyle LaFleche, Tom Swayne.



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